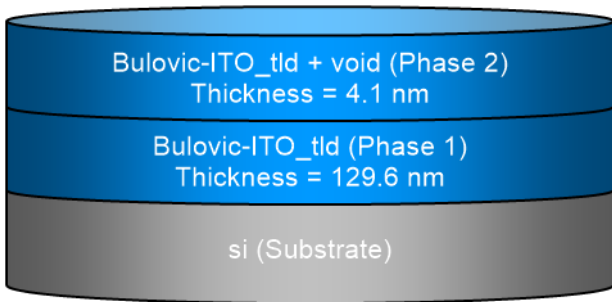


## SEA regression report summary

Sample ID
001b 65° 1
001b 70° 2
001b 75° 3

Details	
Software and regression log	
Software about	Semilab - Spectroscopic Ellipsometry Analyzer - SEA
Software version	1.7.1
Officially licensed to	MIT
Operator	operator
Date and time of regression	26-08-2021 15:36
Comments	

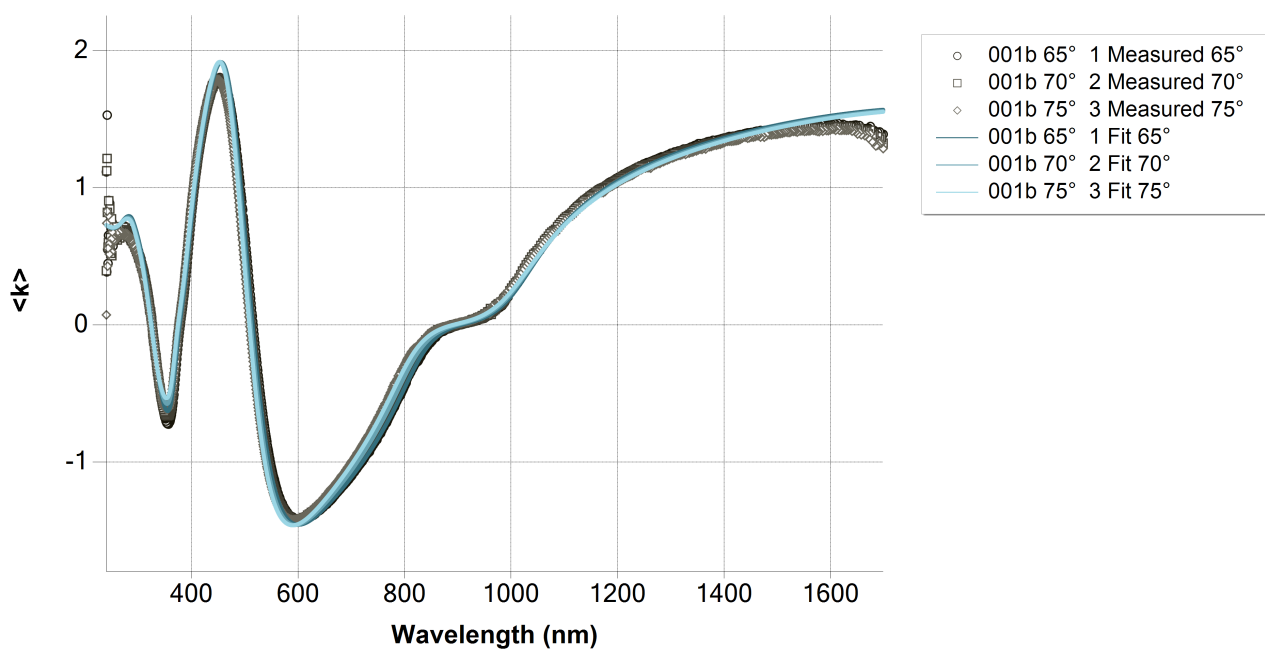
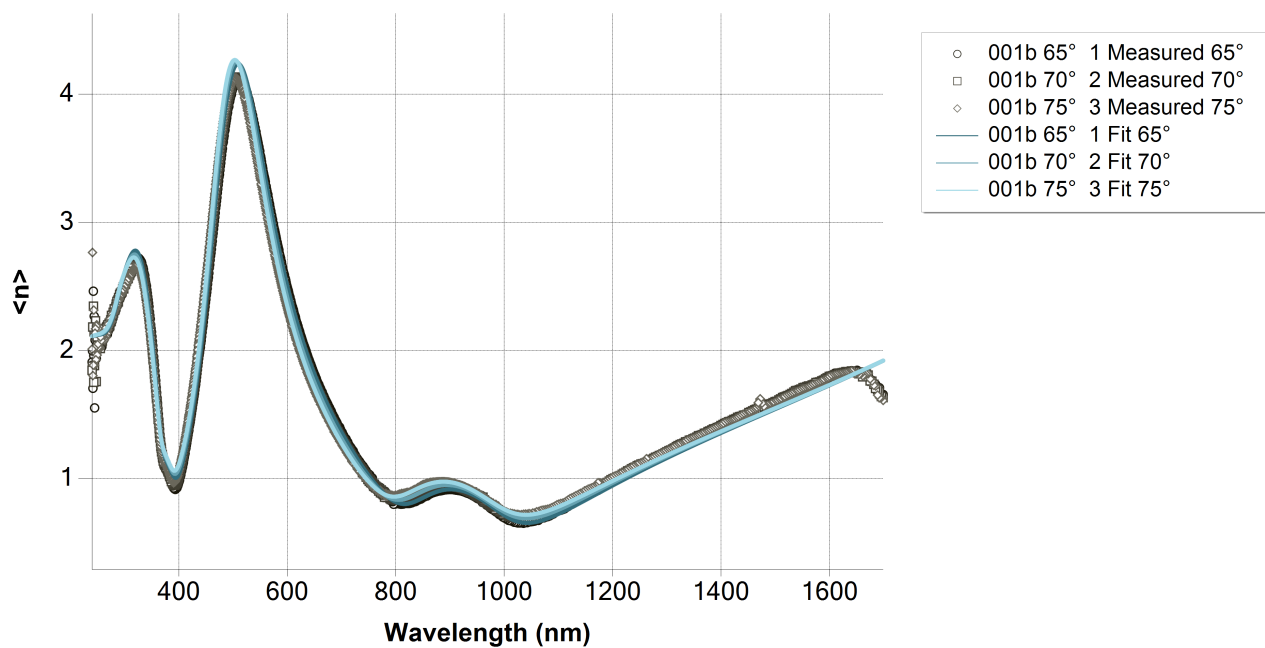
Layer structure	
Overview	
 <p>The diagram illustrates a three-layer structure. The top layer is labeled 'Bulovic-ITO_tld + void (Phase 2)' with a thickness of 4.1 nm. The middle layer is labeled 'Bulovic-ITO_tld (Phase 1)' with a thickness of 129.6 nm. The bottom layer is labeled 'si (Substrate)'.</p>	
Optical model	
Phase 2	Bulovic-ITO_tld + void
Diffusion	
Phase 1	Bulovic-ITO_tld
Dispersion law	Tauc-Lorentz
	Drude

## Regression results

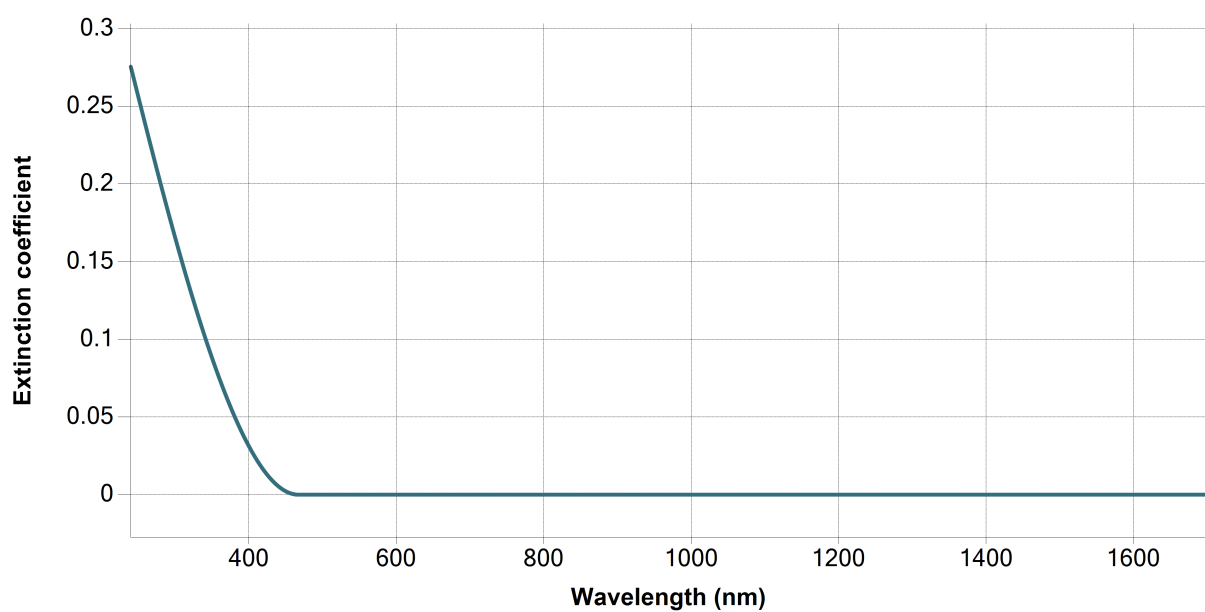
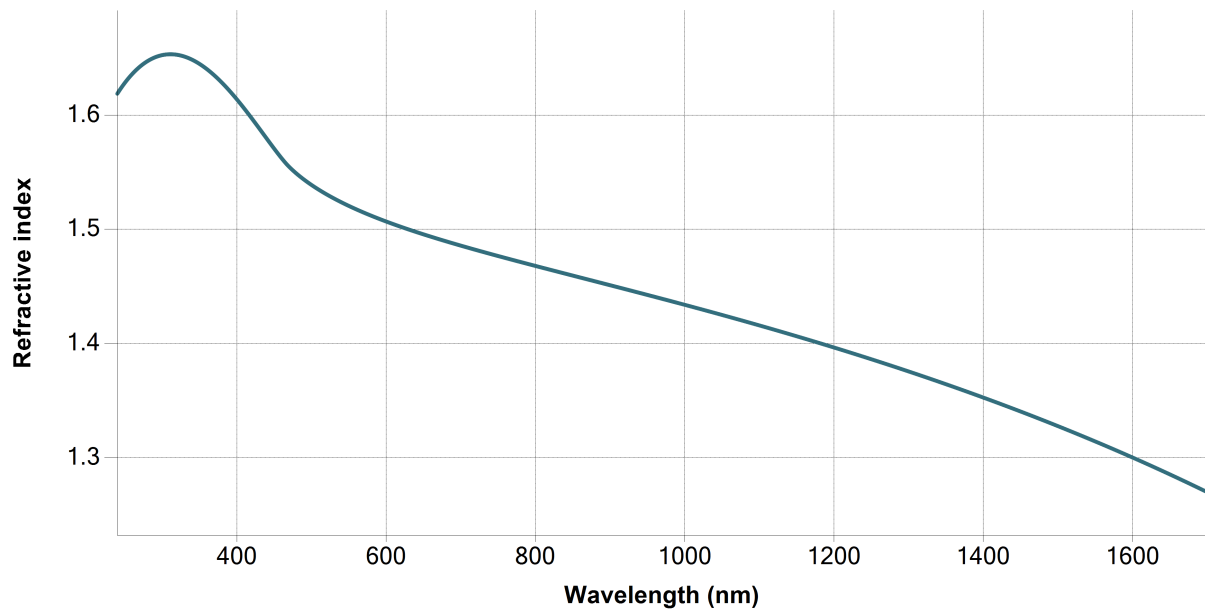
Measurement information				
Measurement 1				
Measurement file path	C:\Users\emmabat\lito-si\001b.smdx			
Angle of Incidence	65°			
Measurement 2				
Measurement file path	C:\Users\emmabat\lito-si\001b.smdx			
Angle of Incidence	70°			
Measurement 3				
Measurement file path	C:\Users\emmabat\lito-si\001b.smdx			
Angle of Incidence	75°			
Regression details				
Regression 1 (EllipsoReflectance)				
Wavelength range	239.84 - 1698.83 nm			
Angle of Incidence	65°			
Fit to	<n>, <k>			
Regression 2 (EllipsoReflectance)				
Wavelength range	239.84 - 1698.83 nm			
Angle of Incidence	70°			
Fit to	<n>, <k>			
Regression 3 (EllipsoReflectance)				
Wavelength range	239.84 - 1698.83 nm			
Angle of Incidence	75°			
Fit to	<n>, <k>			
Angular Aperture	0°			
Fit algorithm	LMA			
Results				
Parameters	Value	Fitted	2 σ confidence limit	Unit
Model				
AOI Shift	0			°
Angular Aperture	0			°
Phase 2 (Bulovic-ITO_tld + void)				
Thickness	4.058	X	0.092869	nm
Depolarization coefficient	0.33333			
Concentration 1	0.5			
Concentration 2	0.5			
Phase 1 (Bulovic-ITO_tld)				
Thickness	129.563	X	0.14566	nm
A (eV)	285.98226	X	14.61448	eV
E0 (eV)	9.45509	X	0.11405	eV
C (eV)	40.28278	X	2.43197	eV
Eg (eV)	2.65438	X	0.008447	eV
E_p (eV)	0.96892	X	0.0050786	eV
E_Γ (eV)	0			eV
Eps_inf	0			
Derived parameters	Value			

Phase 2 (Bulovic-ITO_tld + void)		
n @ 632.8 nm	1.4992	
k @ 632.8 nm	0	
Phase 1 (Bulovic-ITO_tld)		
n @ 632.8 nm	2.0563	
k @ 632.8 nm	0	
Substrate (si)		
n @ 632.8 nm	3.8811	
k @ 632.8 nm	0.0195	
Drude derived parameters	Value	Unit
Phase 1 (Bulovic-ITO_tld)		
Conductivity (S/m)	$\infty \pm \text{NaN}$	S/m
Resistivity (m $\Omega$ .cm)	$0 \pm \text{NaN}$	m $\Omega$ .cm
Resistance ( $\Omega$ /sq)	$0 \pm \text{NaN}$	$\Omega$ /sq
N type dopant concentration (at/cm <sup>3</sup> )	$1.7022\text{E}+20 \pm 1.7844\text{E}+18$	at/cm <sup>3</sup>
P type dopant concentration (at/cm <sup>3</sup> )	$2.5192\text{E}+20 \pm 2.6409\text{E}+18$	at/cm <sup>3</sup>
N type dopant mobility (cm <sup>2</sup> /Vs)	$\infty \pm \text{NaN}$	cm <sup>2</sup> /Vs
P type dopant mobility (cm <sup>2</sup> /Vs)	$\infty \pm \text{NaN}$	cm <sup>2</sup> /Vs
Fit quality		
R <sup>2</sup>	0.9966	
RMSE	0.05487	

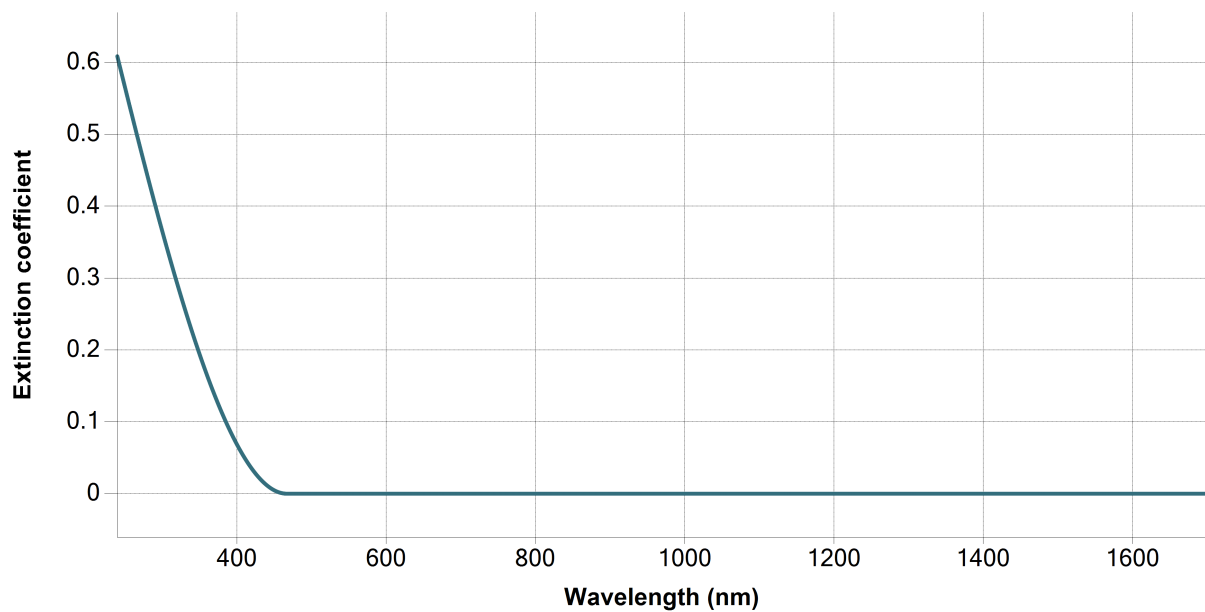
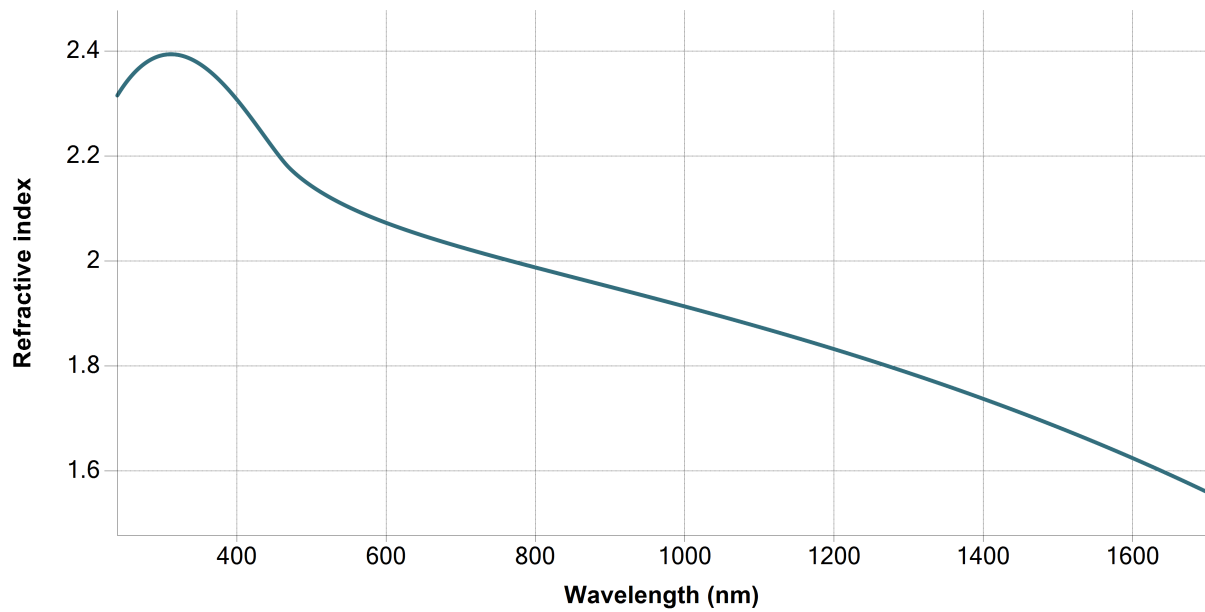
## Regression graphs



## Phase 2 (Bulovic-ITO\_tld + void) - Dispersion graphs



## Phase 1 (Bulovic-ITO\_tld) - Dispersion graphs



## Substrate (si) - Dispersion graphs



Correlation coefficients							
	Ph2 - Bulovic-ITO_tld + void - Thickness	Ph1 - Bulovic-ITO_tld - Thickness	Ph1 - Tauc-Lorentz[1] - A (eV)	Ph1 - Tauc-Lorentz[1] - E0 (eV)	Ph1 - Tauc-Lorentz[1] - C (eV)	Ph1 - Tauc-Lorentz[1] - Eg (eV)	Ph1 - Drude[2] - E_p (eV)
Ph2 - Bulovic-ITO_tld + void - Thickness	1	-0.4233	-0.1046	0.0443	-0.1015	-0.0175	-0.0964
Ph1 - Bulovic-ITO_tld - Thickness		1	0.0094	0.0256	0.0449	0.0109	-0.3061
Ph1 - Tauc-Lorentz[1] - A (eV)			1	-0.166	0.9682	0.8799	0.4455
Ph1 - Tauc-Lorentz[1] - E0 (eV)				1	0.0822	-0.4887	0.2474
Ph1 - Tauc-Lorentz[1] - C (eV)					1	0.7578	0.4905
Ph1 - Tauc-Lorentz[1] - Eg (eV)						1	0.3041
Ph1 - Drude[2] - E_p (eV)							1